

### **Amendments to the Specification**

Please amend the specification as follows:

Please **replace** the paragraph at page 7, lines 17-19 (paragraph 0058 of U.S. Patent Publication 2004/0017743), with the following replacement paragraph:

As described hereinafter in detail, the recording characteristic analyzing unit 5 can measure each ~~characteristics~~ characteristic corresponding to each of the parameters ~~in two~~ by two different methods.

Please **replace** the paragraph at page 9, lines 23-25 (paragraph 0076 of U.S. Patent Publication 2004/0017743), with the following replacement paragraph:

In addition, as understood from FIG. 3, a position at which the  $\beta$  (beta) value is maximized and that at which the spherical aberration is approximately minimized substantially ~~coincides~~ coincide with each other.

Please **replace** the paragraph at page 10, lines 32-36 (paragraph 0085 of U.S. Patent Publication 2004/0017743), with the following replacement paragraph:

In each of the signals S5, a level corresponding to the top pulse Tp of the recording pulse RP shown in FIG. 4C becomes a write level Lw, a level corresponding to the multi pulses Mp of the recording pulse RP shown in FIG. 4C becomes a pit level Lp, and a ~~level~~ level corresponding to the bias level B of the recording pulse RP shown in FIG. 4C becomes a read level Lr.

Please **delete** the paragraph at page 20, lines 13-20 (paragraph 0151 of U.S. Patent Publication 2004/0017743).